ANSI/OESC TAG to ISO/TC 172/SC 1 Annual Report for 2010

Prepared by TAG/SC 1 Leader: Dave Aikens

Number of Meetings Held during 2010: 1

Date: October 12, 2010

Location: BSR, London, England

Number of Meetings Scheduled for 2011: 1

Date: October 2011

Location: Kyoto, Japan

List any significant accomplishments for ANSI/OEOSC TAG/SC 1 this year.

In 2010, SC1 published four standards. Three of these, ISO 9336-1 on optical transfer function, ISO 10110-8 on surface texture notations, and ISO 15529 on MTF, were revisions to existing standards, and the fourth, ISO 25297-1, the NODIF information model, was a new standard. The United States led the revision of the first two standards.

More important, perhaps, was the decision to withdraw or cancel six projects, and begin work consolidating ISO 10110-2, 3, and 4 for glass imperfection notations, as well as many of the ISO 9022 Environmental standards. We view this reduction and consolidation as an important aspect of making standards affordable and relevant.

In addition, new projects have been initiated for a standard set of roughness artefacts, data reduction for roughness and waviness measurements on optics, fixing the OTF standard, and revising several parts of ISO 10110 (Parts 1, 10, 5, 6, and 12). Of these new projects, the United States is project leader on five of them, and is a primary contributor to the other three.

List any problems encountered by the ANSI/OEOSC TAG/SC 1 during the year

Not a problem so much as an observation. There is increasing resistance to revising the drawing notations standards to be more consistent with standard practice in the United States. Specifically in the areas of how glass is specified on drawings, and how surface imperfections are specified and evaluated, are being opposed by the German delegation. When this is combined with the Japanese agenda to not change anything unless there is no choice, and with the loss of active participation by the UK and France, we may not be successful in the coming years as we have been in the last five.